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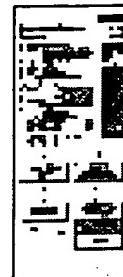
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**>Title:** [JP2000345041A2: COMPOSITION FOR FORMING FILM, PRODUCTIC COMPOSITION FOR FORMING FILM, AND MATERIAL FOR FORMIN INSULATION FILM](#)

**Derwent Title:** Composition for film formation for production of semiconductors, comprises a product of hydrolysis and condensation obtained by hydrolyzing and condensing organosilicon compound(s) [\[Derwent Record\]](#)

**Country:** JP Japan**Kind:** A2 Document Laid open to Public inspection

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**Assignee:** JSR CORP  
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**Published / Filed:** 2000-12-12 / 1999-06-04

**Application Number:** JP1999000158674**IPC Code:** C08L 83/04; C08K 5/06; H01L 21/312; H01L 21/316;**Priority Number:** 1999-06-04 JP1999000158674

**Abstract:** PROBLEM TO BE SOLVED: To obtain a composition having improved storage stability and giving a film improved in uniformity, permittivity, and leak current characteristics by selecting a composition containing a hydrolyzate of a silane compound or a condensate of the hydrolyzate and having a specified propylene glycol content.

SOLUTION: This composition contains at least either of a hydrolyzate and/or a condensate selected from a compound of formula I and a compound of formula II and a solvent of formula III of a purity of 99% (as measured by gas chromatography) and has a propylene glycol content of 10,000 ppm or below. In the formula, R<sub>1</sub> is H, F, or a monovalent organic group; R<sub>2</sub> to R<sub>6</sub> are each a monovalent organic group; a, b, and c are each 0-2; R<sub>7</sub> is O or -(CH<sub>2</sub>)<sub>n</sub>; in formula II, n is 1-6; d is 0 or 1; R<sub>8</sub> and R<sub>9</sub> are each a monovalent organic group selected from H, a 1-4C alkyl, and CH<sub>3</sub>CO-; and e is 1-2. The composition desirably has an iron content and a sodium content each of which is 15 ppb or below and may contain a  $\beta$ -diketone, a compound having a polyalkylene oxide structure, or the like.

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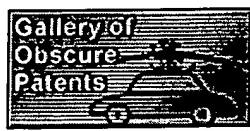
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<input checked="" type="checkbox"/>	JP2000345041A2	2000-12-12	1999-06-04	COMPOSITION FOR FORMING FILM PRODUCTION OF COMPOSITION FOR FORMING FILM, AND MATERIAL FO FORMING INSULATION FILM
<input checked="" type="checkbox"/>	EP1058274B1	2005-07-27	2000-05-31	Composition for film formation and ma insulating film formation
<input checked="" type="checkbox"/>	EP1058274A1	2000-12-06	2000-05-31	Composition for film formation and ma insulating film formation
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